

Electronic structure and hydrogen absorption in Mg-Ni alloy thin films

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The strong interest in pure Mg and Mg-based alloys as hydrogen storage materials is associated with the fact that magnesium can absorb a large amount of hydrogen. Moreover, magnesium is abundant, light weight, and relatively not expensive [1]. Magnesium based thin film materials are subject of intensive studies due to a potential application as switchable mirrors and hydrogen sensors [1,2]. In this contribution we report on electronic structure and room temperature (RT) hydrogen absorption in Mg-Ni alloy thin films. Mg-based alloy thin films were prepared on transparent glass substrates at RT by UHV RF/DC magnetron co-sputtering. Before hydrogenation, all samples were coated with a 10 nm thick Pd layer. The chemical composition of all the layers and interface mixing between Mg-Ni and Pd layers were studied in-situ using X-ray photoelectron spectroscopy (XPS). Furthermore, the XPS valence bands were measured for all the prepared alloy thin films. Hydrogen absorption in Mg-Ni alloy thin films were studied at a pressure of about 1000 mbar using simultaneous optical transmittance and four-point resistivity measurements. Moreover, before and after hydrogen absorption the samples were characterised by Atomic Force Microscopy and high-angle X-ray diffraction (XRD). XPS measurements showed no surface segregation effect in freshly prepared Mg-Ni alloy thin films. On the other hand, successive measurements of the XPS Mg-2p, Ni-2p and Pd-3d peaks for Mg₂Ni thin films covered by Pd layer revealed a formation of interface Mg-Pd alloy layer. Such an interface alloy layer can considerably influence on the hydrogen absorption in the Mg₂Ni thin films [2]. Transmittance and resistivity measurements during hydrogen absorption showed that the 100 nm – Mg thin film covered by 10 nm Pd layer needed about 200 h for saturation. The MgNi and MgNi₂ alloy thin films revealed no hydrogen absorption at RT. On the other hand, the fastest rise in transmittance was observed for Mg₂Ni thin film covered by 10nm Pd. The transmittance of the sample with a thickness of about 200 nm reached 90 percent of the maximal value after 40 s of hydrogenation. The sample was completely loaded with hydrogen after about 20 minutes. RT hydrogen absorption in pure Mg and Mg₂Ni alloy thin films was also confirmed by intense hydride reflections observed in the XRD patterns.

References:

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